

AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

LISTING OF CLAIMS:

1. (Cancelled).

2. (Currently amended) AThe polishing medium for chemical-mechanical polishing, comprising an oxidizing agent, a protective-film-forming agent, a water-soluble polymer excluding poly(oxyethylene)lauryl ether, polyvinyl alcohol, gelatin and carboxymethylcellulose, and water according to claim 27, wherein said water-soluble polymer has a weight-average molecular weight of 500 or more.

3. (Previously presented) The polishing medium for chemical-mechanical polishing according to claim 2, wherein said water-soluble polymer comprises two or more polymers each having a weight-average molecular weight of 500 or more, wherein but a weight-average molecular weight of said polymers are different from each other.

4. – 19. (Cancelled).

20. (Currently amended) The polishing medium for chemical-mechanical polishing according to claim 227, wherein said water-soluble polymer has a weight-average molecular weight of 1,500 or more.

21. (Currently amended) The polishing medium for chemical-mechanical polishing according to claim 227, wherein said water-soluble polymer has a weight-average molecular weight of 5,000 or more.

22. – 32. (Cancelled).

33. (Previously presented) A polishing medium for chemical-mechanical polishing, comprising an oxidizing agent, a protective-film-forming agent, a water-soluble polymer and water, wherein the water-soluble polymer is at least one selected from the group consisting of alginic acid, pectic acid, agar, curdlan and pullulan.

34. (Cancelled).

35. (Previously presented) A polishing medium for chemical-mechanical polishing, comprising an oxidizing agent, a protective-film-forming agent, a water-soluble polymer and water, wherein the water-soluble polymer is at least one selected from the group consisting of polyvinyl pyrrolidone and polyacrolein.